

Figure 1. An example of thermal shrinkage of non-coated and ALD- Al_2O_3 -coated separator membranes after annealing at 120°C and 140°C . ALD- Al_2O_3 was deposited using TMA& H_2O and TMA& O_3 processes.

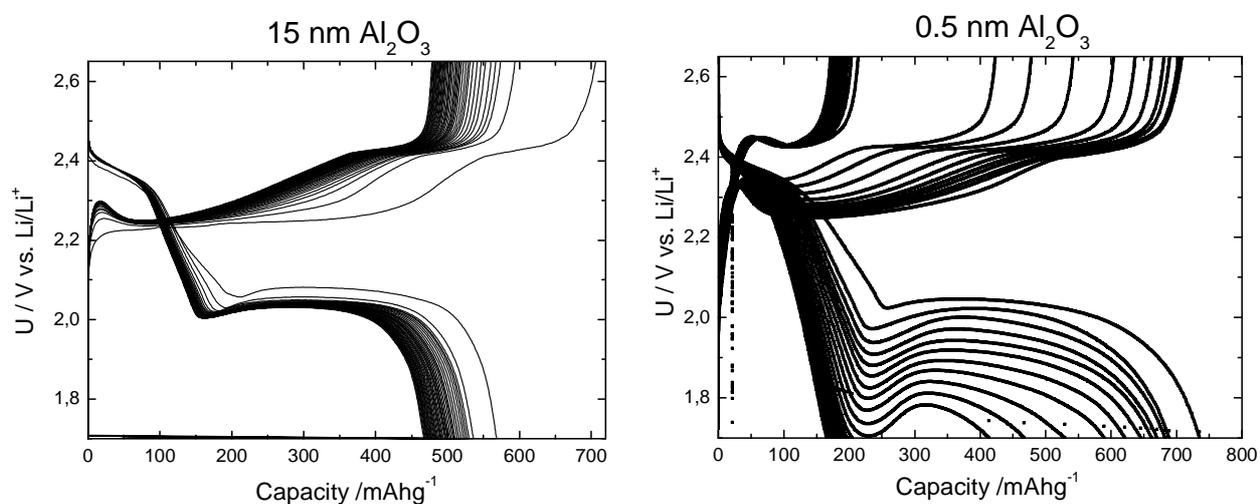


Figure 2. Charge and discharge profiles when cycling the electrochemical cell assembled with ALD-coated separator of (a) 15nm and (b) 0.5nm thickness of ALD- Al_2O_3 .